

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	31996	(bump pad) same (resist photoresist polyimide polymer\$2 organic resin\$4) same (opening hole groove trench recess\$4 depress\$4 aperture window)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/22 10:26
L2	7203	1 and (project\$4 recess\$4 depress\$4 notch\$3 tooth teeth finger) same (resist photoresist polyimide polymer\$2 organic resin\$4) same (opening hole groove trench aperture window)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/22 10:28
L3	660	2 and (resist photoresist polyimide polymer\$2 organic resin\$4) near7 (opening hole groove trench aperture window) near5 (project\$4 recess\$4 depress\$4 notch\$3 tooth teeth finger)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/22 10:30
L4	15	3 and (resist photoresist polyimide polymer\$2 organic resin\$4) near7 (opening hole groove trench aperture window) near5 ("on" "over" align\$3) near5 (pad bump)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/22 10:33
L5	379	3 and (resist photoresist polyimide polymer\$2 organic resin\$4) near7 (opening hole groove trench aperture window) same (peel\$3 exfoliat\$3 etch\$3 remov\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/22 10:37